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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Wang et al.

Attorney Docket No.: NOVLO85/
NVLS-2875

Application No.: 10/785,235

Examiner: UNASSIGNED

Filed: February 23, 2004

Group: 2812

Title: PLASMA DETEMPLATING AND
SILANOL CAPPING OF POROUS
DIELECTRIC FILMS

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on March 24, 2005 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

Signed: _____


Joyce L. Ferreira**INFORMATION DISCLOSURE STATEMENT**
37 CFR §§1.56 AND 1.97(b)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:


The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. NOVLP085).

Respectfully submitted,

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Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. NOVL085/NVLS-2875 Applicant: Wang et al. Filing Date February 23, 2004	Application No.: 10/785,235 Group 2812
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U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A1	6,391,932	05/21/02	Gore et al.			08/08/00
	A2	5,789,027	08/04/98	Watkins et al.			11/12/96
	A3	5,700,844	12/23/97	Hedrick et al.			04/09/96
	A4	20030157248	08/21/03	Watkins et al.			11/21/02
	A5	20020123240	09/05/02	Gallagher et al.			11/30/01
	A6	20040096672	05/20/04	Lukas et al.			11/14/02
	A7						
	A8						
	A9						
	A10						
	A11						

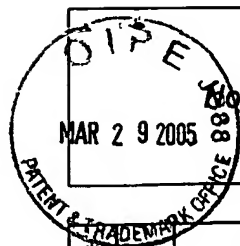
Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B1							

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	Humayun et al., "Method For Forming Porous Films By Porogen Removal Combined With In Situ Modification", U.S. Patent No. 10/404,693, filed March 31, 2003, Office Action dated March 15, 2005
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

**Notice of References Cited**

Application/Control No. 10/404,693	Applicant(s)/Patent Under Reexamination HUMAYUN ET AL.	
Examiner Brian K Talbot	Art Unit 1762	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2003/0157248	08-2003	Watkins et al.	427/256
	B	US-6,391,932	05-2002	Gore et al.	521/61
	C	US-2002/0123240	09-2002	Gallagher et al.	438/781
	D	US-5,700,844	12-1997	Hedrick et al.	521/77
	E	US-5,789,027	08-1998	Watkins et al.	427/250
	F	US-6,444,715	09-2002	Mukherjee et al.	521/64
	G	US-2004/0096672	05-2004	Lukas et al.	428/446
	H	US-6,329,017	12-2001	Liu et al.	427/240
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
*	U	Cho et al., "Plasma treatments of molecularly templated nanoporous silica films", Electrochemical and Solid State Letters, 4(4) G35-G38 (2001)			
	V				
	W				
	X				

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.